



US00D959058S

(12) **United States Design Patent**
Chen

(10) **Patent No.:** **US D959,058 S**

(45) **Date of Patent:** **** Jul. 26, 2022**

(54) **MASK**

D601,308 S * 9/2009 Broersma D29/122
D654,633 S * 2/2012 Anderson D29/108
D826,478 S 8/2018 Chen

(71) Applicant: **Bor Jye Enterprise Co., Ltd.**, Tainan (TW)

FOREIGN PATENT DOCUMENTS

(72) Inventor: **Chun-Nan Chen**, Tainan (TW)

CN 3456257 * 6/2005

(73) Assignee: **Bor Jye Enterprise Co., Ltd.**, Tainan (TW)

OTHER PUBLICATIONS

(**) Term: **15 Years**

Evike Valken Annex MI-3 Airsoft Paintball Full Face Mask, available in Amazon.com, date first available Jan. 25, 2016 [online], [site visited Mar. 16, 2022], Available from the internet URL: https://www.amazon.com/dp/B01B2441PC/ref=cm_sw_em_r_mt_dp_WS8GCZ0FQ67E7NQMPQT3?_encoding=UTF8&psc=1 (Year: 2016).*

(21) Appl. No.: **29/764,640**

Virtue VIO XS II Thermal Paintball Goggles_Masks, available in Amazon.com, date first available Feb. 11, 2019 [online], [site visited Mar. 16, 2022], Available from the internet URL: https://www.amazon.com/dp/B07ZQQMGPD/ref=cm_sw_em_r_mt_dp_GKQXXHV8C5TZZFBNJ0MV?_encoding=UTF8&th=1 (Year: 2019).*

(22) Filed: **Dec. 31, 2020**

(51) **LOC (13) Cl.** **29-02**

(52) **U.S. Cl.**
USPC **D29/108**

(58) **Field of Classification Search**
USPC D2/870, 872, 878; D29/100, 102, 103, D29/104, 105, 106, 107, 108, 110, 122
CPC .. A41D 13/11; A42B 3/04; A42B 3/18; A42B 3/20; A42B 3/185; A42B 3/226; A42B 3/0406; A61F 9/06; A61F 9/029; A63B 2071/105; A63B 71/08; A63B 71/10
See application file for complete search history.

* cited by examiner

Primary Examiner — Jennifer L Rempfer
Assistant Examiner — Elizabeth Anne Glassberg
(74) *Attorney, Agent, or Firm* — Alan D. Kamrath; Karin L. Williams; Mayer & Williams PC

(56) **References Cited**

U.S. PATENT DOCUMENTS

D407,858 S * 4/1999 Cyr D29/108
6,381,749 B1 * 5/2002 Cyr A42B 3/20
2/427
6,957,447 B1 * 10/2005 Broersma A63B 71/10
2/427
D522,697 S * 6/2006 Chen D29/108
D526,094 S * 8/2006 Chen D29/108
D529,234 S * 9/2006 Broersma D29/108
D555,837 S * 11/2007 Chen D29/110
D570,551 S * 6/2008 Broersma D29/108
D570,552 S * 6/2008 Broersma D29/110
D571,050 S * 6/2008 Broersma D29/108
D586,050 S * 2/2009 Chen D29/110

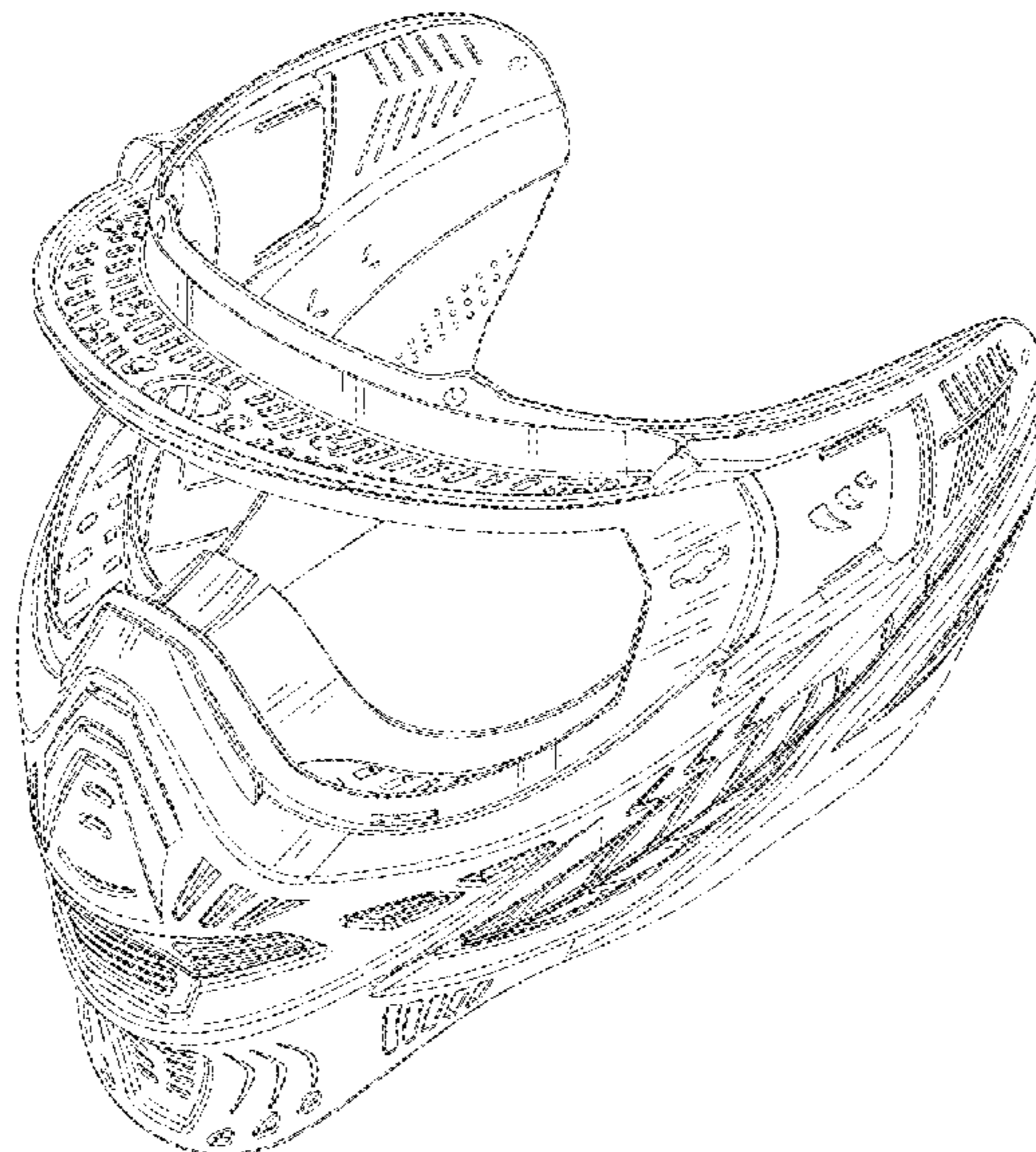
(57) **CLAIM**

The ornamental design for a mask, as shown and described.

DESCRIPTION

FIG. 1 is a perspective view of a mask showing my design. FIG. 2 is a front elevational view thereof. FIG. 3 is a rear elevational view thereof. FIG. 4 is a left side elevational view thereof. FIG. 5 is a right side elevational view thereof. FIG. 6 is a top plan view thereof; and, FIG. 7 is a bottom plan view thereof.

1 Claim, 7 Drawing Sheets



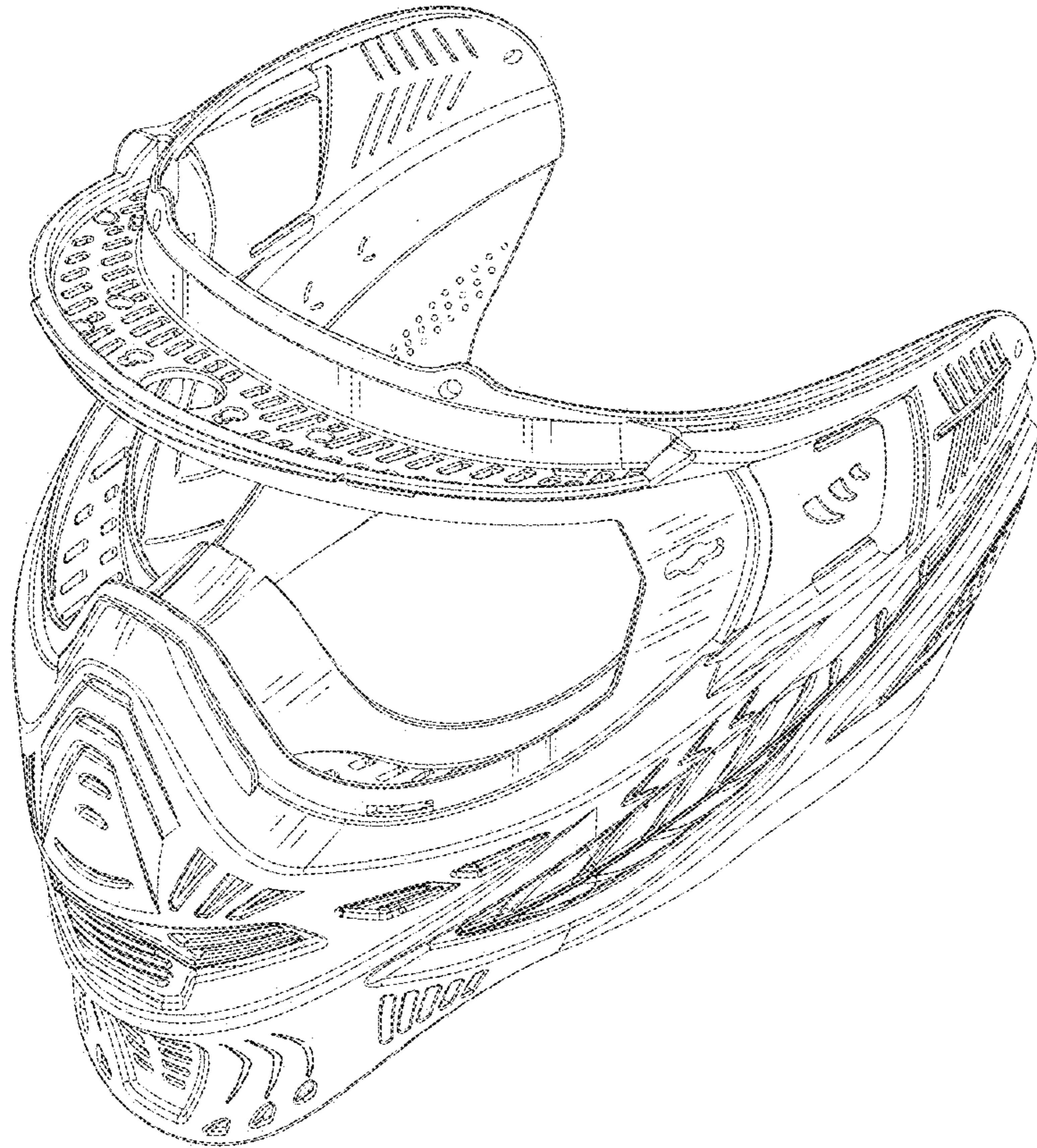


FIG. 1

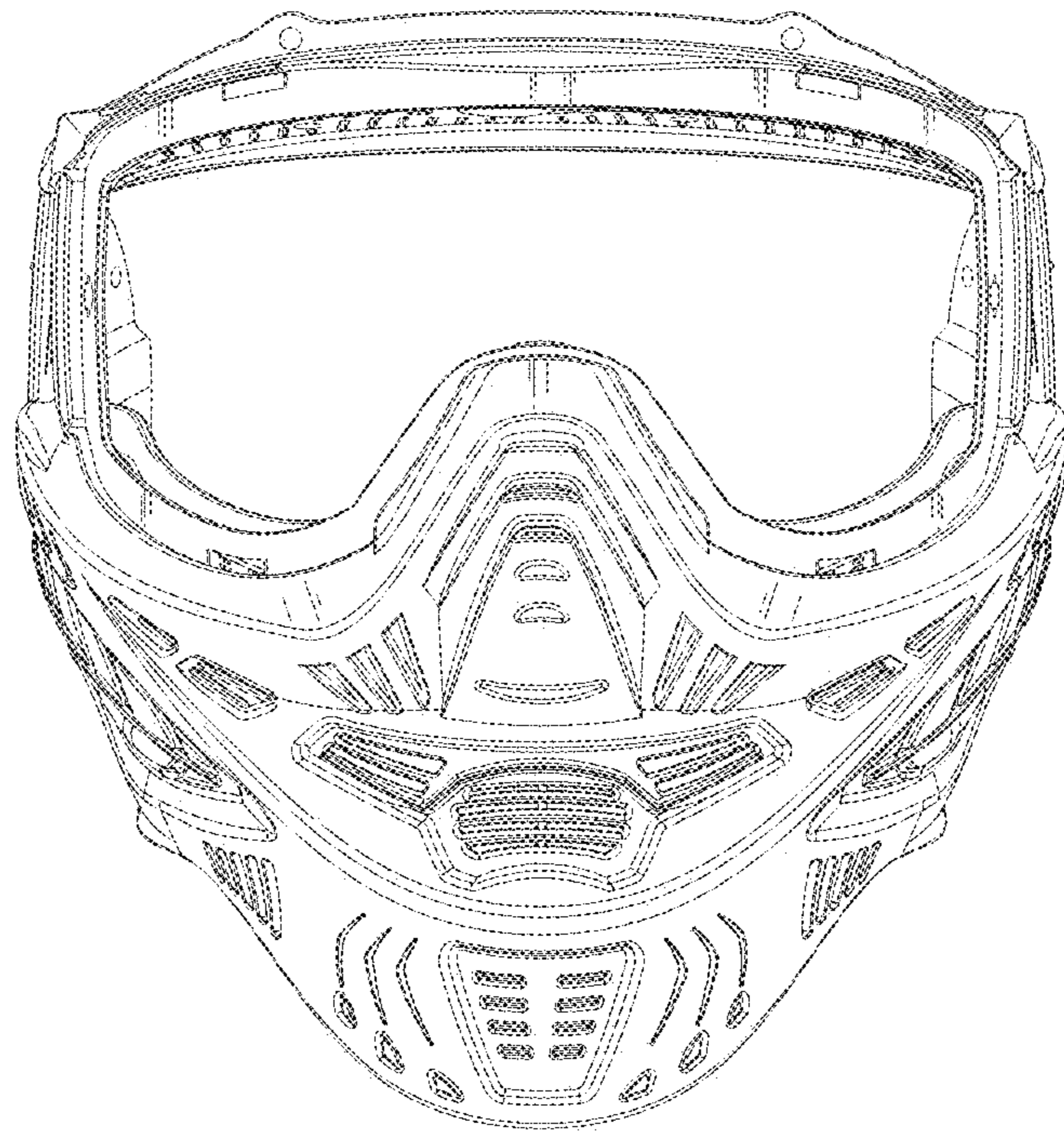


FIG. 2

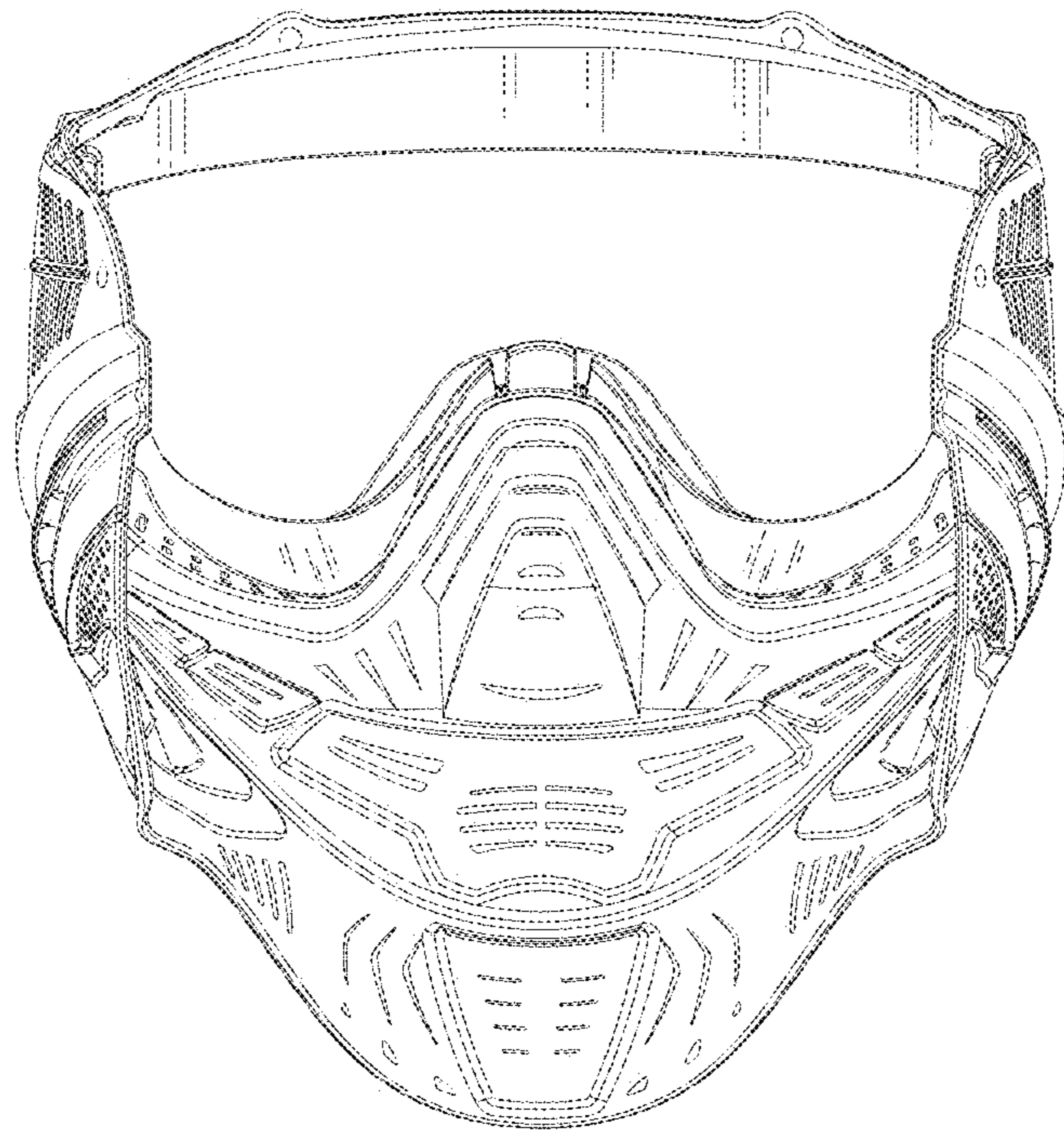


FIG. 3

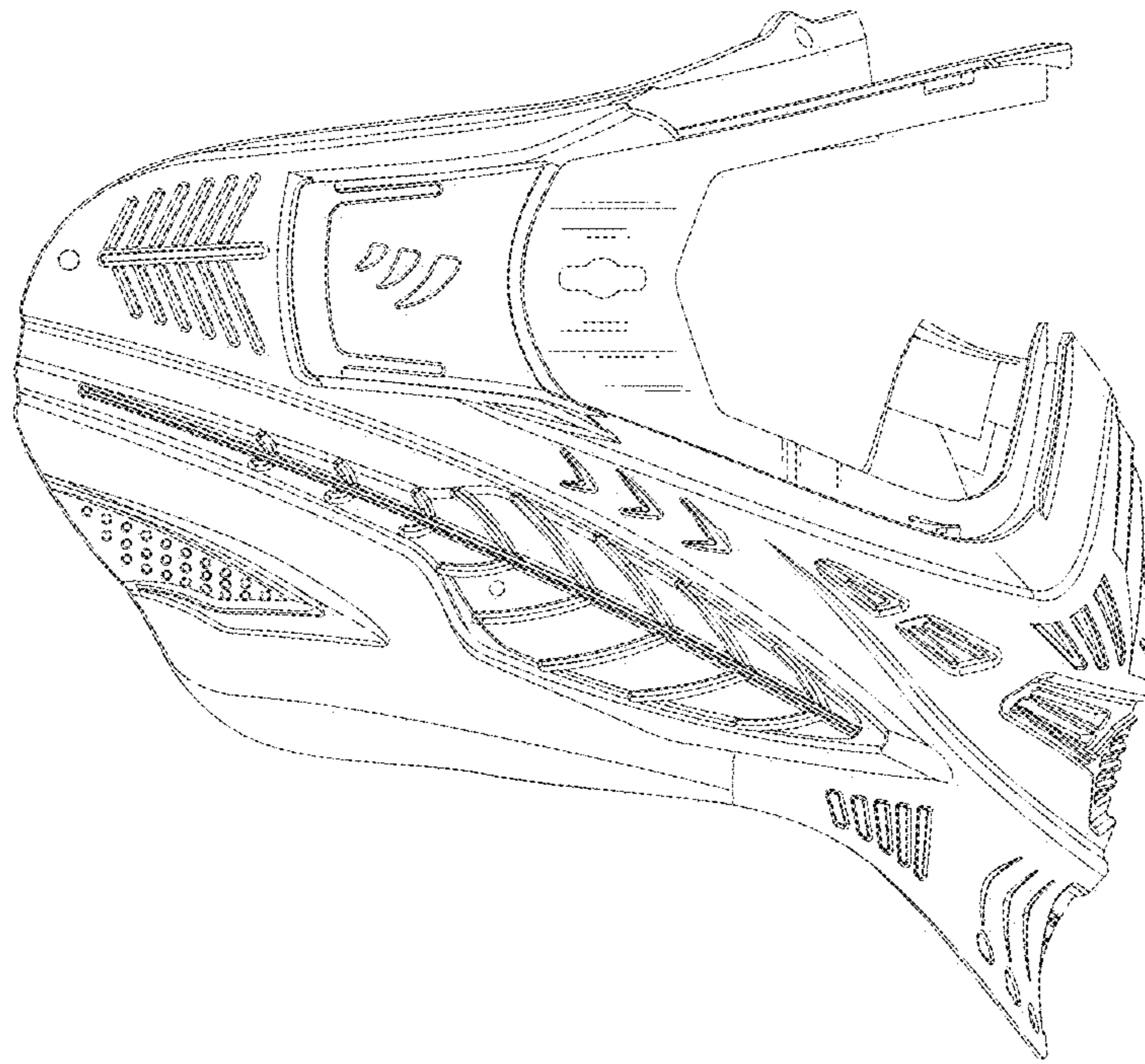


FIG. 4

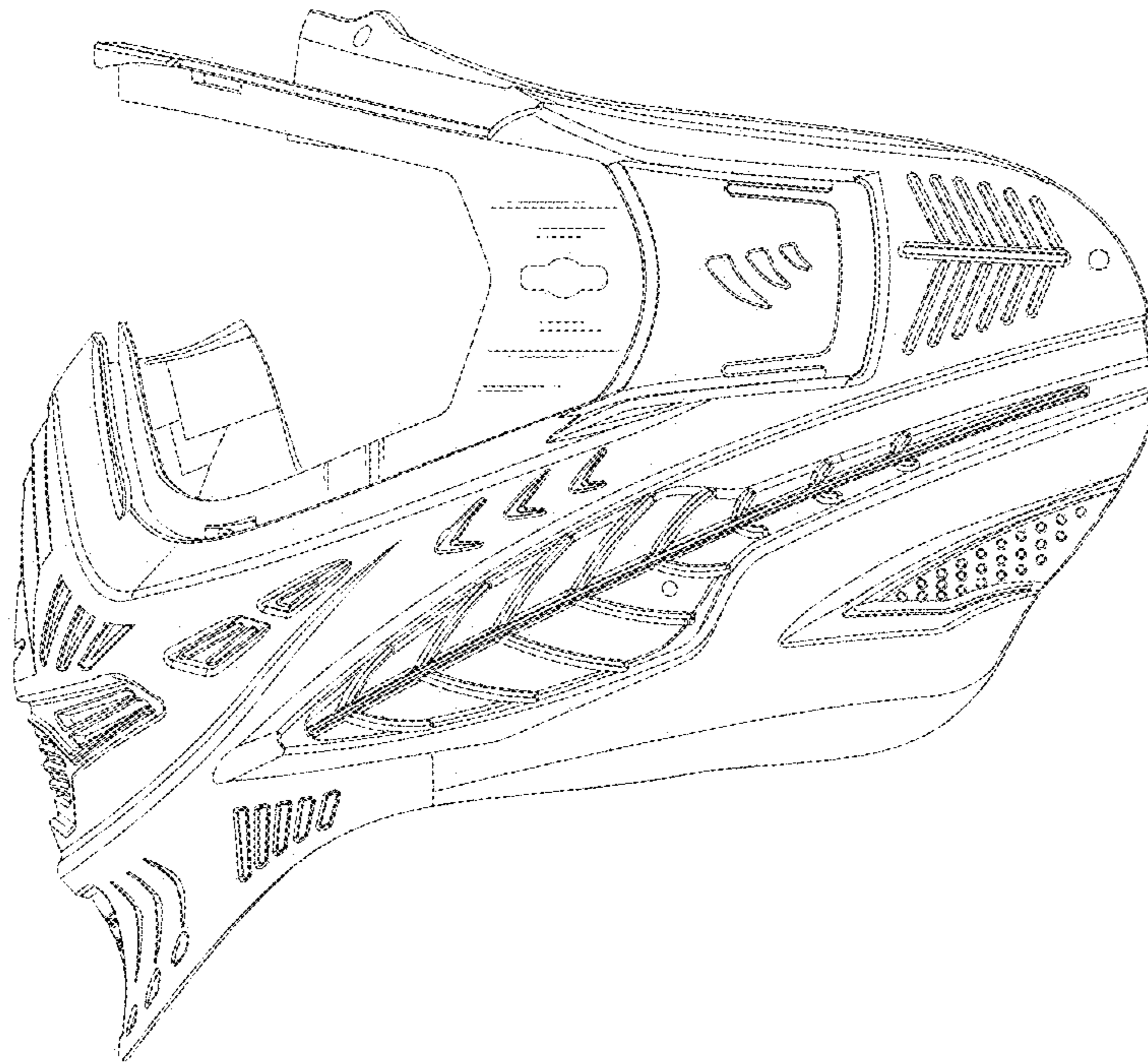


FIG. 5



FIG. 6

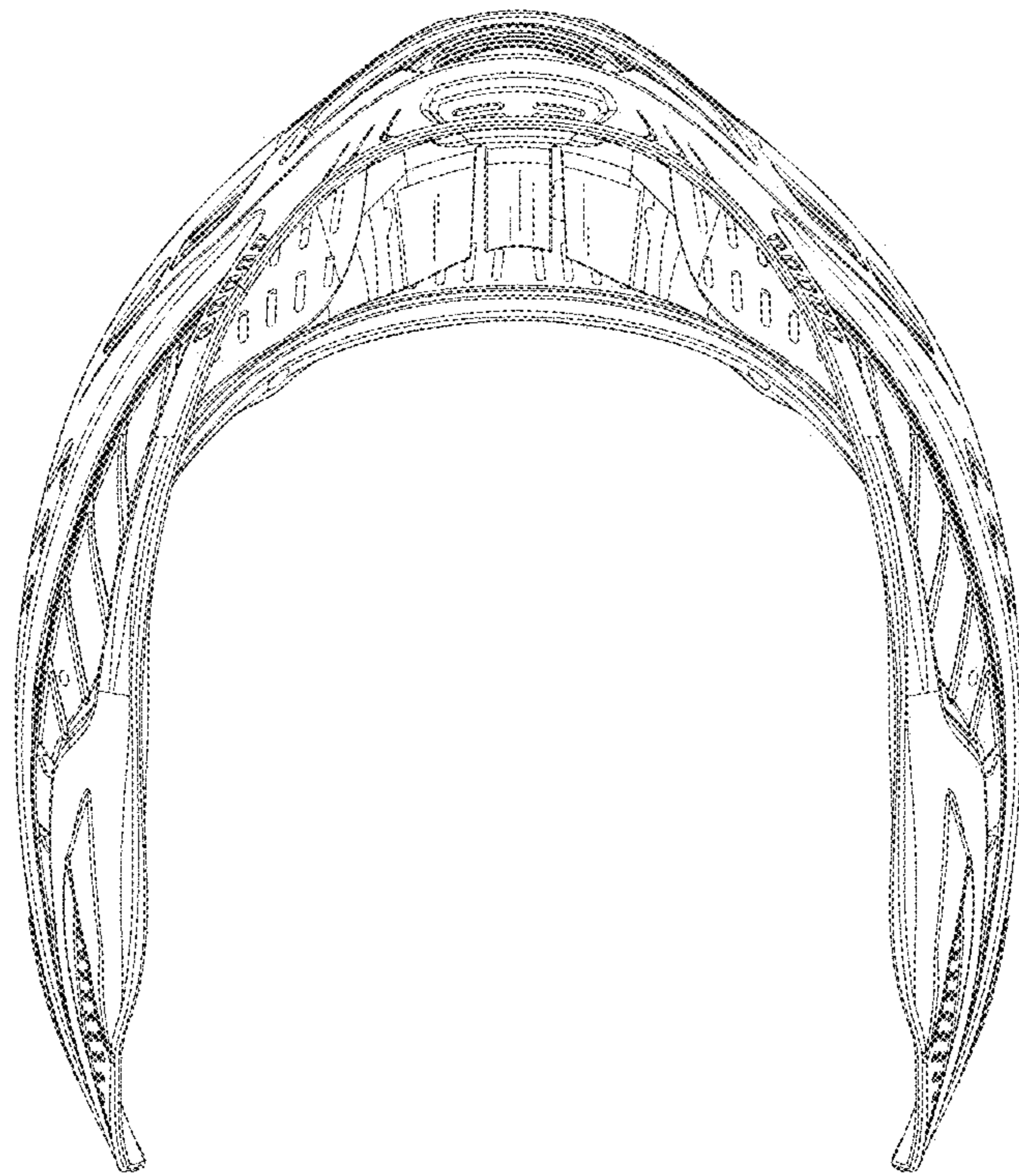


FIG. 7